

ABSTRACT

~~Exposure~~ An exposure apparatus EX exposes a substrate ~~P~~ through a liquid ~~LQ~~ liquid. The exposure apparatus is provided with a substrate stage ~~PST~~ which can hold the ~~substrate P~~ substrate, an interferometer ~~system (43)~~ system, which projects a measuring light on a reflecting plane formed on a moving mirror on the substrate stage ~~PST~~ stage, receives the reflected light and measures position information of the substrate stage ~~PST~~ stage, and a ~~memory MRY~~ memory, which stores ~~error~~ error information of the reflecting plane under the condition where the liquid is supplied on the substrate stage as first information. The measurement process using the interferometer system and exposure are performed at high accuracy in the immersion exposure area.